

Dirk-Oliver Detjen

**Characterization and Modeling
of Si-Si Bonded Hydrophobic Interfaces
for Novel High-Power BIMOS Devices**

Bibliographic information published by Die Deutsche Bibliothek

Die Deutsche Bibliothek lists this publication in the Deutsche Nationalbibliografie; detailed bibliographic data is available in the internet at <http://dnb.ddb.de>.

Zugl.: Aachen, Techn. Hochsch., Diss., 2004

AACHENER BEITRÄGE DES ISEA

Herausgeber:

Universitätsprofessor Dr. Rik W. De Doncker
Leiter des Instituts für Stromrichtertechnik und
Elektrische Antriebe der RWTH Aachen (ISEA)
52056 Aachen

D 82 (Diss. RWTH Aachen)

Copyright Shaker Verlag 2004

All rights reserved. No part of this publication may be reproduced, stored in a retrieval system, or transmitted, in any form or by any means, electronic, mechanical, photocopying, recording or otherwise, without the prior permission of the publishers.

Printed in Germany.

ISBN 3-8322-2963-9

ISSN 1437-675X

Shaker Verlag GmbH • P.O. BOX 101818 • D-52018 Aachen

Phone: 0049/2407/9596-0 • Telefax: 0049/2407/9596-9

Internet: www.shaker.de • eMail: info@shaker.de

In this work, the suitability of silicon-silicon bonding for fabrication of new thyristor-type power electronic devices is investigated. A systematic investigation of the bonding interface, particularly in bipolar semiconductor structures, is performed. A detailed analysis of the grain boundary physics in unipolar and bipolar structures is presented for the thermal equilibrium state as well as non-equilibrium state. Based on grain boundary physics, an analytical model of the bonding interface is developed, which allows the calculation of the voltage-current characteristics in bipolar device structures. Moreover, the grain boundary characteristics predicted by the physical analysis and the model are verified by wafer bonding experiments as well as finite-element simulations.

In addition, new concepts for combined bipolar-MOSFET devices are proposed based on the direct wafer bonding technology. A disc-type MOS-Turn-Off Thyristor (MTO) structure is presented where MOSFETs are integrated into the thyristor structure using Si-Si bonding. Hence, the proposed structure enables outstanding switching performance comparable to monolithically integrated designs. The turn-off process can further be optimized by the Double-Gated MTO structure proposed in this work, which enables switching off both emitters of the thyristor structure. Finally, even bidirectional power devices can be realized using Si-Si bonding as demonstrated with a Double-Gated MCT device structure. Finite-element simulation results of the proposed high-power BIMOS device structures are presented verifying their excellent device characteristics.